

Recipe Categories for the LAB 600 H

	Substrate Holder	Chamber Temperature	Ion source
HRN	Higher position	Room T°	No Ion source
HHN	Higher position	High T°	No Ion source
LRN	Lower position	Room T°	No Ion source
LRI	Lower position	Room T°	Ion Assisted Deposition
LRI+N	Lower position	Room T°	Ion source cleaning before deposition (LRN)
LHN	Lower position	High T°	No Ion source
LHI	Lower position	High T°	Ion Assisted Deposition
n-st.	Nanostencil	Room T°	No Ion source